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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/527,683	03/11/2005	Tsuyoshi Takahashi	267417US26PCT 7309	
22850	7590 11/30/2005		EXAM	INER
OBLON, S	PIVAK, MCCLELLA	ESTRADA, MICHELLE		
	1940 DUKE STREET ALEXANDRIA, VA 22314			PAPER NUMBER
	,		2823	
			DATE MAILED: 11/30/2005	

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)			
-	10/527,683	TAKAHASHI ET AL.			
Office Action Summary	Examiner	Art Unit			
	Michelle Estrada	2823			
The MAILING DATE of this communication appears on the cover sheet with the correspondence address Period for Reply					
A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) OR THIRTY (30) DAYS, WHICHEVER IS LONGER, FROM THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication. - If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication. - Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).					
Status					
1) Responsive to communication(s) filed on 11 March 2005.					
2a) This action is FINAL . 2b) ☑ This	action is non-final.				
3) Since this application is in condition for allowance except for formal matters, prosecution as to the ments is					
closed in accordance with the practice under Ex parte Quayle, 1935 C.D. 11, 453 O.G. 213.					
Disposition of Claims					
4) Claim(s) 1-10 is/are pending in the application.					
4a) Of the above claim(s) is/are withdrawn from consideration.					
5) Claim(s) is/are allowed.					
6)⊠ Claim(s) <u>1-10</u> is/are rejected.					
7) Claim(s) is/are objected to.					
8) Claim(s) are subject to restriction and/or election requirement.					
Application Papers					
9)☐ The specification is objected to by the Examine	ır.				
10)☐ The drawing(s) filed on is/are: a)☐ acc	epted or b) \square objected to by the $\mathfrak l$	Examiner.			
Applicant may not request that any objection to the					
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).					
11) The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.					
Priority under 35 U.S.C. § 119					
12)⊠ Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). a)⊠ All b)□ Some * c)□ None of:					
 Certified copies of the priority documents have been received. 					
2. Certified copies of the priority documents have been received in Application No					
3. Copies of the certified copies of the priority documents have been received in this National Stage					
application from the International Bureau (PCT Rule 17.2(a)).					
* See the attached detailed Office action for a list of the certified copies not received.					
Attachment(s)					
1) Notice of References Cited (PTO-892)	4) Interview Summary				
 2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) 	Paper No(s)/Mail Da 5)	atent Application (PTO-152)			
Paper No(s)/Mail Date <u>9/26/05</u> .	6) Other:				

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DETAILED ACTION

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 1-10 are rejected under 35 U.S.C. 103(a) as being unpatentable over Jang et al. (2004/0051134) in view of the following comments.

Re claim 1, Jang et al. Disclose forming a base insulating film 130 on a substrate; and forming a high-k dielectric film (410) on the base insulating film, wherein the high-k dielectric film forming step includes: a first step of depositing, in the processing vessel, dielectric film under a first condition so as to the high-k allow a residence time the metal organic compound to extend to a first value (Page 3, paragraphs [0024] and [0025]; and a second step for further depositing the high-k dielectric film under a second condition so as to allow the residence time of the metal organic compound to extend to a second value (Page 3, paragraph [0025]).

Jang does not clearly disclose a specific residence time and that the second value of residence time is smaller than the first value.

Re claims 1-3 and 6-10, one of ordinary skill in the art would have been led to the recited residence time, pressure, flow rate and temperature through routine experimentation to achieve a desired rate of reaction and a desired dielectric thickness. In addition, the selection of residence time, pressure, flow rate and temperature, its

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obvious because it is a matter of determining optimum process conditions by routine experimentation with a limited number of species of result effective variables. These claims are prima facie obvious without showing that the claimed ranges achieve unexpected results relative to the prior art range. In re Woodruff, 16 USPQ2d 1935, 1937 (Fed. Cir. 1990). See also In re Huang, 40 USPQ2d 1685, 1688 (Fed. Cir. 1996)(claimed ranges or a result effective variable, which do not overlap the prior art ranges, are unpatentable unless they produce a new and unexpected result which is different in kind and not merely in degree from the results of the prior art). See also In re Boesch, 205 USPQ 215 (CCPA) (discovery of optimum value of result effective variable in known process is ordinarily within skill or art) and In re Aller, 105 USPQ 233 (CCPA 1995) (selection of optimum ranges within prior art general conditions is obvious).

Note that the specification contains no disclosure of either the critical nature of the claimed residence time, pressure, flow rate and temperature or any unexpected results arising therefrom. Where patentability is said to be based upon particular chosen residence time, pressure, flow rate and temperature or upon another variable recited in a claim, the Applicant must show that the chosen residence time, pressure, flow rate and temperature are critical. *In re Woodruf*, 919 F.2d 1575, 1578, 16 USPQ2d 1934, 1936 (Fed. Cir. 1990).

Re claim 4, Jang et al. disclose wherein the high k dielectric film is a crystalline film, and in the first step, crystalline nuclei of the high k dielectric film are formed on the surface, the same conditions are treated in the same manner.

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Re claim 5, Jang et al. Disclose wherein the metal organic compound is an organic compound containing Hf or Zr, and the high-k dielectric film is HfO2 or ZrO2 film (See table II).

Conclusion

The prior art made of record and not relied upon is considered pertinent to applicant's disclosure.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Michelle Estrada whose telephone number is 571-272-1858. The examiner can normally be reached on Monday through Friday.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Matthew Smith can be reached on 571-272-1907. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is 571-272-2800.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should

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you have questions on access to the Private PAIR system, contact the Electronic

Business Center (EBC) at 866-217-9197 (toll-free).

Michelle Estrada
Patent Examiner
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November 22, 2005